



## Corres. and Mail \*

## RESPONSE UNDER 37 C.F.R. § 1.116 EXPEDITED PROCEDURE REQUESTED EXAMINING GROUP 2813

PATENT

Customer No. 22,852 Attorney Docket No. 08244.0032

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:	)
Sung-Chan PARK et al.	) Group Art Unit: 2813
Application No.: 09/998,303	) Examiner: Nguyen, Thanh T.
Filed: December 3, 2001	) )
For: METHOD FOR FORMING CONTACT HOLE AND SPACER OF SEMICONDUCTOR DEVICE	) Confirmation No.: 4821 )

**Mail Stop AF** 

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

## REQUEST FOR RECONSIDERATION AFTER FINAL

In reply to the Final Office Action mailed October 11, 2005, the period for response extending through January 11, 2006, Applicants request reexamination and reconsideration of the above-identified application based on the following remarks.

Remarks begin on page 2 of this paper.

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